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(84) Designated contracting states:	(74) Representative:

(54) PHOTORESIST
COMPOSITION

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(57) Abstract:

PURPOSE: To obtain a photoresist compsn. having satisfactory defoaming ability and not causing uneven coating or leaving an uncoated part.

CONSTITUTION: This photoresist compsn. contains a fluorine-contg. surfactant having 15-24.5dyn/cm surface tension at the critical micelle concn. in a

photoresist solvent or a fluorine-contg. surfactant made of a polymer having at least one of nonionic, anionic and cationic groups, a fluoroalkyl group and a silicone group in each molecule.

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